

REMARKS

Claims 1, 2 and 4-5 are pending and under consideration in the above-identified application and Claims 3 and 6 were previously cancelled.

In the Office Action, Claims 1, 2 and 4- 5 were rejected.

In this Amendment, Claim 1 is amended. No new matter has been introduced as a result of this Amendment.

Accordingly, Claims 1, 2, 4 and 5 remain at issue.

I. 35 U.S.C. § 103 Obviousness Rejection of Claims 1-2 and 4-6

Claims 1-2 and 4-6 were rejected under 35 U.S.C. § 103(a) as being unpatentable over *Tsuda et al.* (“*Tsuda*”) (U.S. Patent No. 5,936,688) in view of *Nakamura et al.* (“*Nakamura*”) (U.S. Patent No. 5,847,789), and in further view of *Itoh et al.* (“*Itoh*”) (U.S. Patent No. 6,094,252). Although, Applicants respectfully traverse this rejection, to further prosecution, Claim 1 has been amended to clarify the invention and remove any ambiguities that may have been at the basis of this rejection.

Claim 1 is directed to a method of manufacturing a diffusing reflector.

In the relevant part, Claim 1 recites

“said first resin film is patterned by straight connected lines that form a continuous polygonal pattern, said straight lines providing a substantially uniform gap between said adjacent polygonal pillar-shaped bodies thereby forming a rectilinear honeycomb-like pattern,

said gap having a size equal to about a minimum resolution of said photolithography, and
a thickness of the second resin is about 500nm.”

Referring to Applicants’ Figure 2, adjacent pillar-shaped bodies isolated from each other by polygonal patterning a resin film with photolithography are separated by a continuous and substantially uniform gap thereby forming a rectilinear honeycomb-like pattern. The width or size of the gap between any two adjacent polygonal pillar-shaped bodies is set to about 1 μ m which is almost equal to the minimum resolution of the photolithography process.

This is clearly unlike *Tsuda*, *Nakamura*, and *Itoh* taken singly or in combination with each other.

This Examiner states that *Tsuda* discloses the resin film (34a) is patterned by straight connected lines that form a continuous polygon pattern and points to Column 13, lines 33 – 40 for support.

However, as illustrated in FIGs. 6G – 6J, 9H – 9L, 20H – 20L, and 21G – 21J of *Tsuda*, the dimples (pillar-shaped bodies), being either circular or polygonal, are too sparsely distributed or formed on the supporting substrate to form a continuous and substantially uniform concave gap having a size equal to about a minimum resolution of the photolithography between any two adjacent pillar-shaped bodies thereby forming a rectilinear honeycomb-like pattern, after the reflow process, as required by Claim 1.

Moreover, the claimed second resin film has a thickness of about 500nm, which when formed in the gap having a size equal to about a minimum resolution of the photolithography, provides a concave gap between any two adjacent isolated pillar-shaped bodies. As such, upper end portions of any two adjacent isolated pillar-shaped bodies are higher than a lower end portion of the concave gap in the thickness direction of the diffusing reflector, thereby minimizing an occurrence of a flat surface area on the substrate.

As the Examiner acknowledged, *Tsuda* teaches that the least interval (gap) between the resultant adjacent protrusions (pillar-shaped bodies) 112b is as small as about 0.5 μ m. As such, a second resin formed in this gap with a thickness of 500 nm creates a flat gap between the pillar-shaped bodies, rather than a concave gap as required by Claim 1.

Further, both *Nakamura* and *Itoh* also fail to teach or suggest this gap limitation of Claim 1.

Thus, Claim 1 is patentable over *Tsuda*, *Nakamura*, and *Itoh* taken singly or in combination with each other, as are dependent Claims 2, 4 and 5, for at least the same reasons.

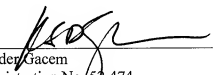
II. Conclusion

In view of the above amendments and remarks, Applicant submits that Claims 1, 2, 4 and 5 are clearly allowable over the cited prior art, and respectfully requests early and favorable notification to that effect.

Respectfully submitted,

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